

PATENT

Atty. Dkt. No. AMAT/2601.P11/PPC/ECP/RKK

IN THE CLAIMS:

Please cancel claims 24-37, and amend the claims as follows:

1. (Currently Amended) An integrated bevel cleaning (IBC) apparatus, comprising:
 - a transfer position where a substrate is positioned;
 - a rinse position where the substrate is rinsed;
 - an etch position where the edge of the substrate is cleaned;
 - ~~an~~ a linear actuator for positioning the substrate in the transfer position, the rinse position and the etch position; and
 - a plurality of cooperatively movable etchant dispense nozzles coupled to at least one etchant dispensing arm assembly positioned proximate the etch position and rotatably positionable near and away from the substrate, the arm and nozzles being cooperatively configured to dispense an etchant onto the front side and backside of the substrate.
2. (Original) The IBC apparatus of claim 1 further comprising a substrate centering hoop for supporting the substrate in the transfer position.
3. (Currently Amended) An integrated bevel cleaning (IBC) apparatus, comprising:
 - a transfer position where a substrate is positioned;
 - a rinse position where the substrate is rinsed;
 - an etch position where the edge of the substrate is cleaned;
 - ~~an~~ a linear actuator for positioning the substrate in the transfer position, the rinse position and the etch position;
 - a plurality of cooperatively movable etchant dispense nozzles configured to dispense an etchant onto the front side and backside of the substrate;
 - a substrate centering hoop for supporting the substrate in the transfer position;and

PATENT

Atty. Dkt. No. AMAT/2601.P11/PPC/ECP/RKK

a substrate centering hoop rinsing nozzle.

4. (Previously Presented) The IBC apparatus of claim 1 further comprising at least one rinsing nozzle located proximate the rinsing position for rinsing at least an edge region of the substrate.
5. (Previously Presented) The IBC apparatus of claim 4 wherein the at least one rinsing nozzle comprises a plurality of rinsing nozzles positioned to rinse the front side and backside of the substrate.
6. (Previously Presented) The IBC apparatus of claim 1 further comprising at least one slit valve located proximate the transfer position.
7. (Currently Amended) The IBC apparatus of claim 1 ~~wherein the actuator comprises further comprising~~ a spindle assembly for retaining the substrate and rotating the substrate, ~~and a wherein the linear actuator for raising raises and lowering lowers~~ the spindle assembly.
8. (Previously Presented) The IBC apparatus of claim 7 wherein the spindle assembly comprises a vacuum chuck.
9. (Cancelled)
10. (Previously Presented) The IBC apparatus of claim 1, wherein the etchant is applied to an edge exclusion zone of the substrate.
11. (Cancelled)
12. (Previously Presented) The IBC apparatus of claim 1, wherein the at least one etchant dispensing arm assembly comprises a plurality of etchant dispensing arm assemblies.

PATENT

Atty. Dkt. No. AMAT/2801.P11/PPC/ECP/RKK

13. (Previously Presented) The IBC apparatus of claim 12 wherein the plurality of etchant dispensing arm assemblies are cooperatively coupled for simultaneously rotating the plurality of etchant dispensing arm assemblies into a position near the substrate and away from the substrate.

14.-22. (Cancelled)

23. (Previously Presented) The IBC apparatus of claim 13 wherein the plurality of etchant dispensing arm assemblies are cooperatively coupled to a single motor for simultaneously rotating the plurality of etchant dispensing arm assemblies.

24.-37. (Cancelled)